

III Imaging Model, Grating-Based Analysis and Optimization

Balu Santhanam

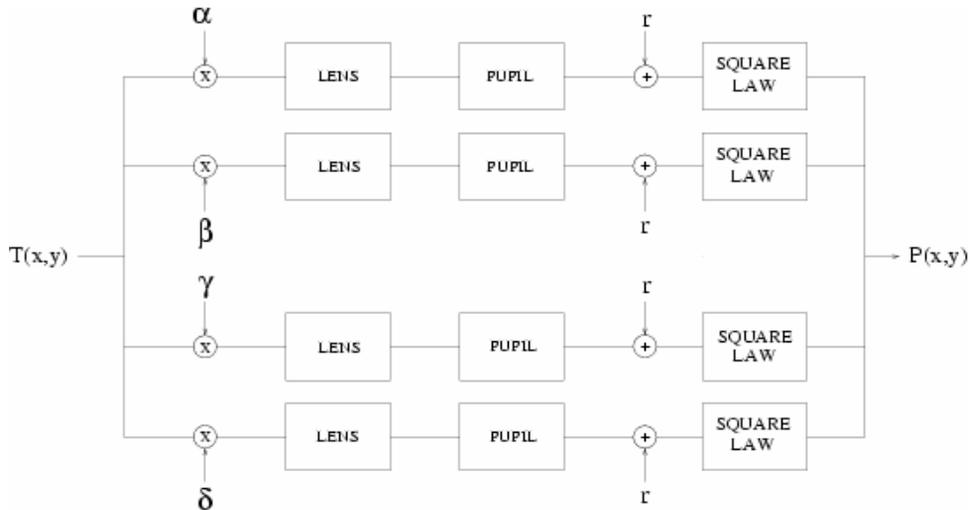
Dept. of EECE, University of New Mexico
Email: bsanthan@eece.unm.edu

Litho MURI
Review-DSIP

- **Optimization for IIL**
 - Frequency coverage
 - Relative intensity ratios
 - Pupil filters
- **Multichannel imaging model**
 - Regularization and restoration
 - Iterative optimization
- **Imaging interferometric microscopy (IIM)**
 - Noise removal and enhancement
 - Exploiting channel redundancy

1. IIL Imaging Model
2. Resolution Enhancement
3. Aerial Image Quality Assessment
4. Grating-based Analysis of IIL
5. Optimization for IIL
6. Multichannel nonlinear image restoration
7. Continuing Research Directions

- Resolution limitations
 - Process latitude
 - NA of optical system
 - Exposure wavelength
- Approaches hitting fundamental limitations
- RET methods: aerial image enhancement



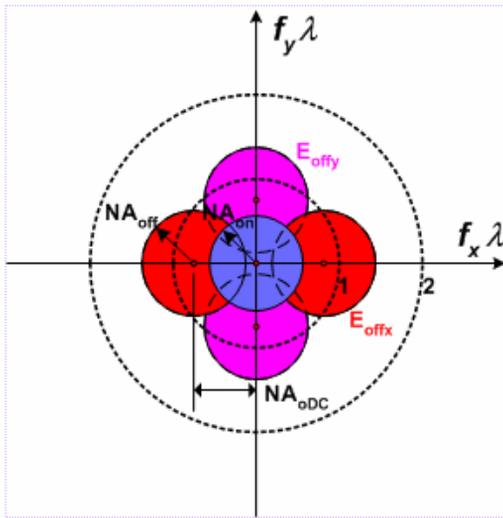
Litho MURI
Review-DSIP

III Imaging Model

$$y = t\{CS(PBD(x) + r)\}$$

- **D** : diagonal matrix of frequency shifts modeling OAI frequency downshifting.
- **B** : lowpass lens filtering operation modeling diffraction limited optics.
- **P** is a diagonal matrix of complex weights modeling pupil filtering.
- **C** the combination operator combines outputs from different channels.
- **S** : magnitude square non-linearity modeling aerial image intensity evaluation from electric field.
- **r**: reference signal, **x**: mask image

Litho MURI
Review-DSIP



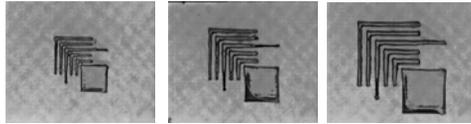
- Coverage parameters: NA_{on} , NA_{off} , NA_{oDC} .
- Tilt angle determines DC offset for off-axis exposure.
- Coverage parameters specify center frequencies and bandwidths of exposures.

Litho MURI
 Review-DSIP

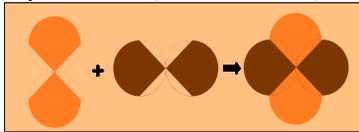
- OPC : boosts strength of higher mask frequencies.
- PSM : modifies phase associated with mask frequencies.
- OAI : tilts axis of illumination allowing access to higher mask frequencies.
- IIL : multiple exposures, frequency down-shifting & up-shifting.
- For large NA systems, IIL is OAI with multiple exposures and pupil filtering.

Litho MURI
 Review-DSIP

I-LINE, NA = 0.04, $f_{\text{offset}} = 0.04/\lambda$

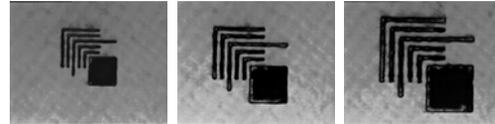


3- μm CD; $\kappa_1 = 0.33$ 4- μm CD 5- μm CD

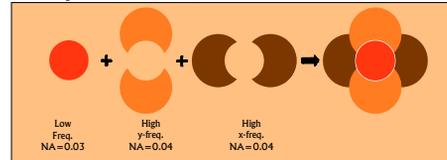


ARO/MURI
 Year3-name-

I-LINE, NA = 0.03/0.04, $f_{\text{offset}} = f_{\text{opt}}$



3- μm CD; $\kappa_1 = 0.33$ 4- μm CD 5- μm CD



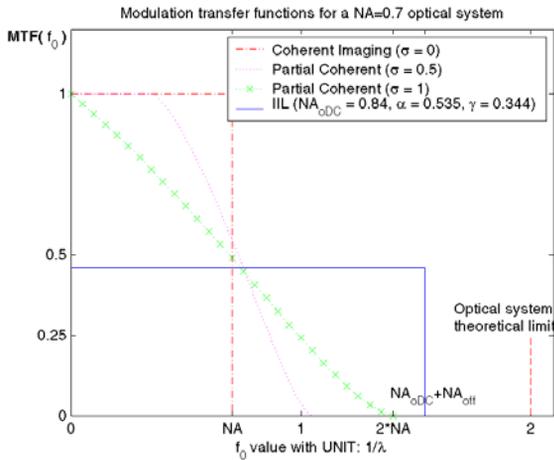
ARO/MURI
 Year3-name-

Litho MURI
 Review-DSIP

Characteristics of IIL

- Different frequency allocation schemes with identical frequency coverage produce different aerial images.
- High frequency information added rather than just providing enhancement of the aerial image.
- Pupil filtering eliminates duplicate frequency coverage and reduces redundancy in the branches.

Litho MURI
 Review-DSIP



- Coherent imaging has limited bandwidth of f_0 .
- Partial coherent illumination (PCI) coverage up to $2f_0$.
- PCI-MTF magnitude decays rapidly after f_0 .
- IIL extends coverage further than PCI.

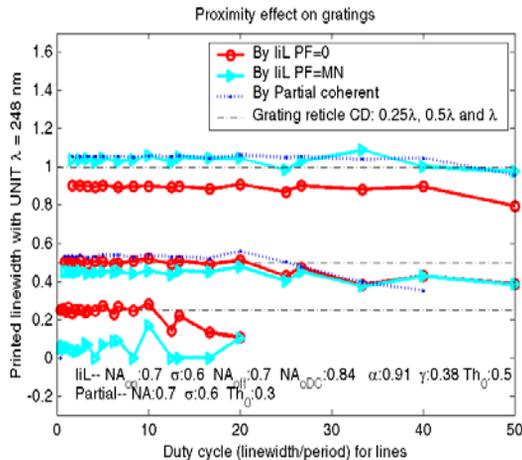
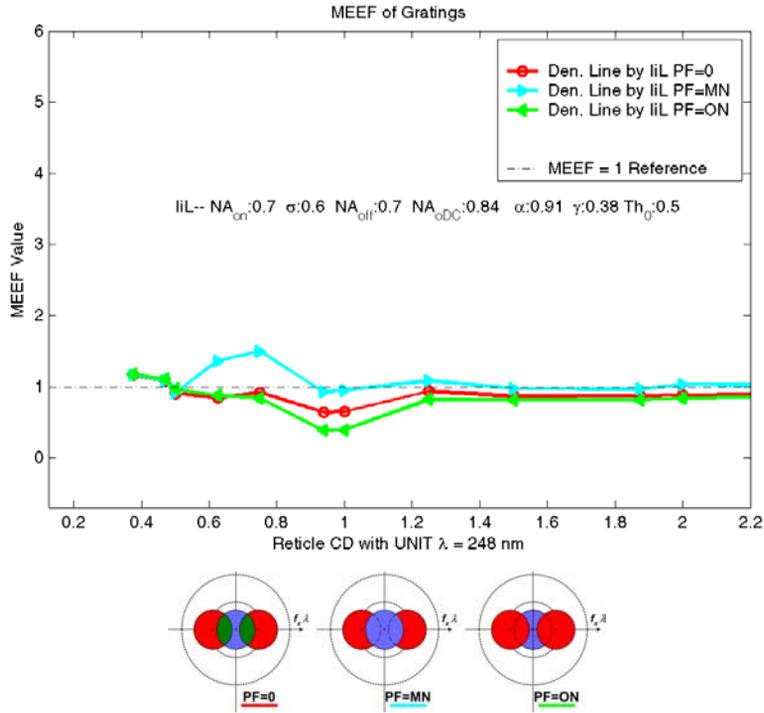
Litho MURI
 Review-DSIP

- MEEF : ratio of change in printed CD to change in mask CD.
- In the linear regime: MEEF approximately 1. For nonlinear regime, i.e., sub-wavelength lithography MEEF is different than 1.
- MEEF > 1 : amplifies mask defects, forces tighter mask tolerances and reduces aerial image quality.
- MEEF for dense patterns different than the MEEF for isolated features: a MEEF gap or bias exists.

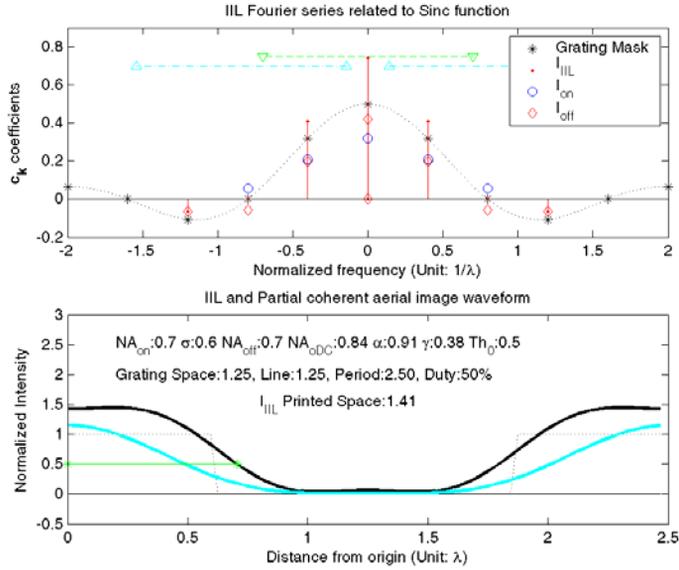
Litho MURI
 Review-DSIP

- Island errors, keyhole errors, break errors, and connectivity errors cause circuit failure.
- Line-edge shortening, line-edge roughness, corner rounding measure aerial image edge quality.
- Line edge shortening , corner rounding affect device speed and performance and line edge roughness causes increased leakage currents.
- Mask error enhancement: amplifies mask defects.

- Motivation: Grating-based analysis could provide clues for ILL analysis, optimization for complicated masks.
- On-axis exposure provides frequency coverage for smaller frequencies up to diffraction limit. Off-axis exposures cover higher frequencies.
- Dense gratings: off-axis exposures provide better higher-frequency coverage than partially-coherent illumination (PCI) method.

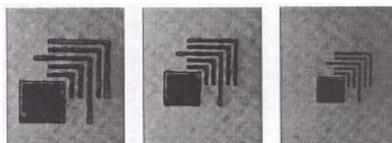
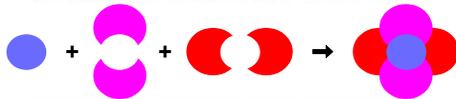
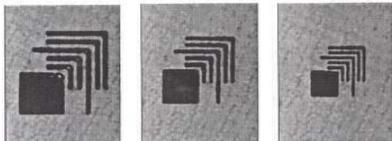


- MEEF for ILL grating simulations smaller than PCI method.
- Extended coverage enables printing of small features where PCI method fails.
- MEEF and printed CD variations occur when mask frequency moves from on-axis to off-axis exposure.



Litho MURI
 Review-DSIP

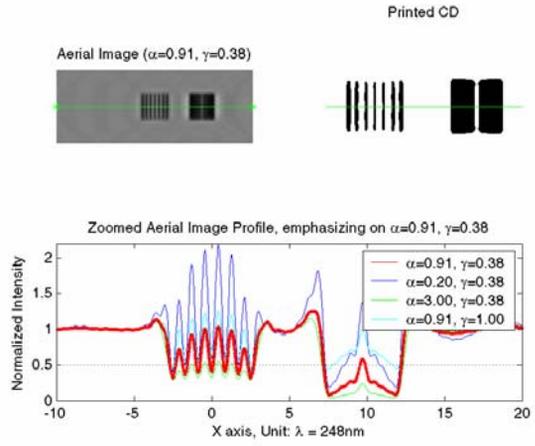
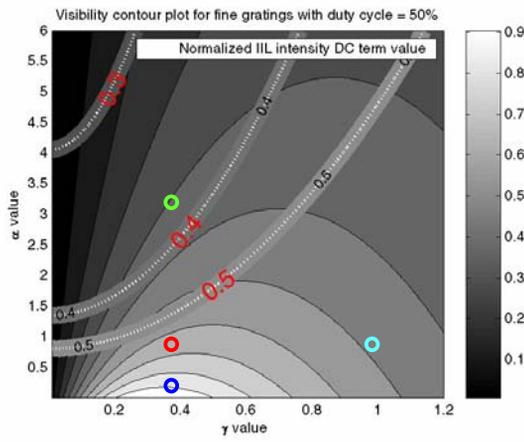
$$I_{IIL}(x, y) = \alpha \cdot I_{on}(x, y) + |E_{off}(x, y) + \gamma|^2$$



- Minimize |MEEF-1|
- Optimize frequency coverage parameters
- Design apodized pupil filters and overlap exposures.
- Optimize intensity ratios.
- Penalize fatal errors heavily.
- Error criteria should reflect aerial image defects

Litho MURI
 Review-DSIP

$$I_{ILL}(x, y) = \alpha \cdot I_{on}(x, y) + |E_{off}(x, y) + \gamma|^2$$



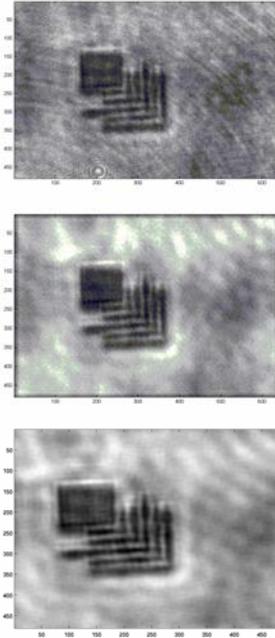
Litho MURI
 Review-DSIP

- Optimize 2 intensity parameters and 3 exposure coverage parameters.
- First optimize relative intensity parameters α, γ to maximize visibility of smallest mask feature.
- With optimized intensities determine appropriate settings for coverage parameters.
- Successively optimize relative intensities and coverage parameters until constraints are met.

Litho MURI
 Review-DSIP

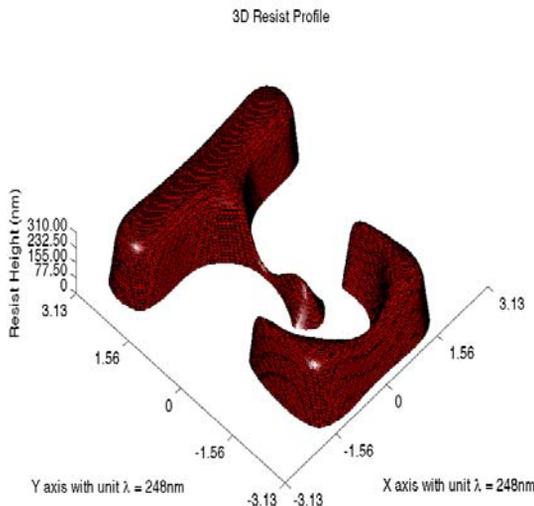
- **Single channel nonlinear regularization framework: linearization, regularization, least-squares.**
- **Iterative implementation of nonlinear regularization uses steepest decent methods.**
- **Multichannel restoration framework: constrained least-squares, exploit cross-channel correlation.**
- **IIL optimization: combination of nonlinear regularization and multichannel restoration.**

- **Cross-channel redundancy introduced by overlapping pupil filters can be exploited in restoration.**
- **Optimization over IIL frequency coverage parameters and relative intensities subject to constraints.**
- **Choice of error norm determines the complexity of optimization.**
- **Nonlinearity : Multimodal error surface with multiple local minima.**



Litho MURI
 Review-DSIP

- Inverse problem: aerial image known and object required.
- Access to individual channel gray scale aerial images.
- Multichannel noise removal and restoration problem.
- Adaptive noise cancellation to remove noise and retain image features.



- Use Gaussian pupil filters to overlap exposures to reduce ripples and improve resolution.
- Apply concepts of quadrature mirror filtering and other filterbank related ideas to IIL.
- Iterative constrained optimization problem.
- Application to imaging interferometric microscopy.
- Incorporating realistic 3D model for photoresist processing into the optimization.

Litho MURI
 Review-DSIP